WHAT IS CLAIMED IS:

1-27. (Canceled)

28. (New) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising:

an input unit which inputs an exposure condition; and

a determining unit which determines whether the substrate should be exposed while scanning the substrate at a changing speed corresponding to a speed within at least one of an acceleration period and a deceleration period in a target speed profile of the substrate, based on the exposure condition.

29. (New) The apparatus according to claim 28, wherein the exposure condition includes at least one of a shot size, a shot layout of an exposure to be performed, an alignment measure, a shot layout of an exposure having been performed, a user's indication, a shot position and an accuracy required with respect to scanning the substrate.

30. (New) The apparatus according to claim 29, further comprising an original stage for holding an original having the pattern and a substrate stage for holding the substrate, wherein the exposure condition includes a synchronization accuracy with respect to scanning said original stage and said substrate stage.

31. (New) A device manufacturing method, comprising:

a step of exposing a substrate to a pattern using an exposing apparatus defined in claim 28.

32. (New) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising:

an evaluation unit which evaluates whether a previous measure with respect to a substrate can be used; and

a determining unit which determines which should be used among at least two exposure methods, based on an evaluation result of said evaluation unit.

33. (New) The apparatus according to claim 32, wherein at least two exposure methods include at least one of (i) a static exposure with the substrate standing still while the substrate is exposed, (ii) a constant speed exposure with the substrate running at a constant speed while the substrate is exposed, and (iii) a changing speed exposure with the substrate running at a changing speed while the substrate is exposed.

34. (New) A device manufacturing method, comprising:

a step of exposing a substrate to a pattern using an exposure apparatus defined in claim 32.

35. (New) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising:

an input unit which inputs an exposure condition; and

a determining unit which determines which should be used among at least two exposure methods, based on the exposure condition,

wherein if a manual mode is specified as one of the exposure conditions, said determining unit performs the determination based on a user's indication.

36. (New) A device manufacturing method, comprising:

a step of exposing a substrate to a pattern using an exposure apparatus defined in claim 35.